



<b>Substitute Form PTO-1449</b> (Modified) <b>Information Disclosure Statement by Applicant</b> (Use several sheets if necessary)  (37 CFR §1.98(b))	<b>U.S. Department of Commerce Patent and Trademark Office</b>	<b>Attorney's Docket No.</b> 05542-516001	<b>Application No.</b> 10/721,769
	<b>Applicant</b> Birang et al.		
	<b>Filing Date</b> November 24, 2003	<b>Group Art Unit</b> 2812	

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
DN	AA	5,081,796	01/1992	Schultz	—	—	—
	AB	5,486,129	01/1996	Sandhu et al.	—	—	—
	AC	5,658,183	08/1997	Sandhu et al.	—	—	—
	AD	5,722,875	05/1998	Iwashita et al.	—	—	—
	AE	5,730,642	03/1998	Sandhu et al.	—	—	—
	AF	5,741,070	04/1998	Moslehi	—	—	—
	AG	5,773,316	06/1998	Kurosaki et al.	—	—	—
	AH	5,840,614	11/1998	Sim et al.	—	—	—
	AI	5,985,094	11/1998	Mosca	—	—	—
	AJ	6,159,073	12/2000	Wiswesser et al.	—	—	—
	AK	6,413,145	07/2002	Pinson, II et al.	—	—	—
DN	AL	6,422,927	07/2002	Zuniga	—	—	—

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
DN	AM	DE 3801969 A	07/1989	DE	—	—	English Abstract	
DN	AN	EP 0879678 A	11/1998	EPO	—	—	—	—
DN	AO	EP 0904895 A	03/1999	EPO	—	—	—	—

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
DN	AP	Wijekoon et al., "Minimization of Metal Loss during Chemical Mechanical Planarization of Copper-Oxide and Copper - Low $\kappa$ Damascene Structures", March 2002, Santa Clara, CA, 4 pp.
	AQ	Ravid et al., "Copper CMP Planarity Control Using ITM", 2000, Rehovoth, Israel, 7 pp.
	AR	Pan et al., "Copper CMP and Process Control", Final Paper submitted to CMP-MIC Conference, February 11-12, 1999, Santa Clara, CA and Cambridge, MA, 7 pp.
DN	AS	Zhang et al., "Automated Process Control of Within-Wafer and Wafer-to-Wafer Uniformity in Oxide CMP", March 2002, Santa Clara, CA, 6 pp.

<b>Examiner Signature</b> 	<b>Date Considered</b> 9/23/05
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	